

# サンアプロの非イオン性光酸発生剤

## Non-ionic Type Photo Acid Generators of SAN-APRO

●自社の蓄積されたデータを基に新しい組成を設計

Design an unprecedented new products based on our accumulated data

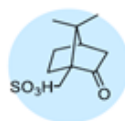
### NA-CS1, NP-SE10 (開発品)

- 弱酸( $pka=1.2$ )と強酸( $pKa=-14$ )それぞれ発生可能

Our products can generate each other of weak acid ( $pka=1.2$ ) and strong acid ( $pKa=-14$ )

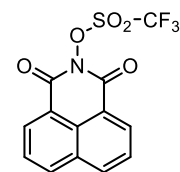
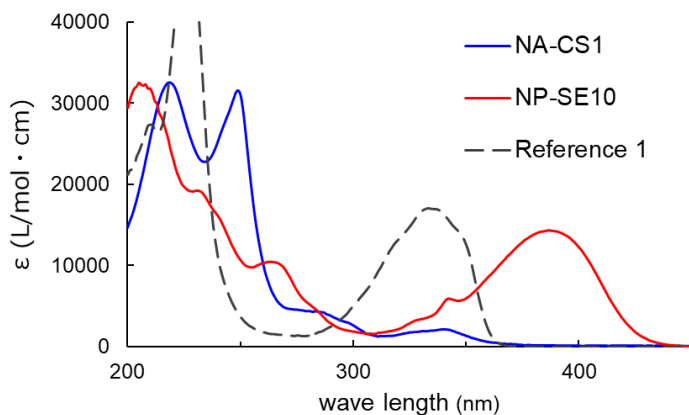
- 高熱安定性 High thermal stability

- 高溶剤溶解性 High solubility



$CF_3SO_3H$

Name	Generated acid	Function
NA-CS1	カンファースルホン酸 ( $pKa=1.2$ )	<ul style="list-style-type: none"><li>i線(365nm)高感度</li><li>高透過率(厚膜に適用可能)</li><li>嵩高い酸のため高解像性が期待</li></ul>
NP-SE10	トリフルオロメタン スルホン酸( $pKa=-14$ )	<ul style="list-style-type: none"><li>長波長対応(365~436nm)</li></ul>



Reference 1  
(CAS RN: 85342-62-7, TCI)

Evaluation method: 0.025mM Acetonitrile sol.



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### 特長 Features

Name		<i>NA-CS1</i>	<i>NP-SE10</i>	Reference 1
Structure		Arylamide	Naphthalimide	
Generated acid		Camphor sulfonic acid	Trifluoromethanesulfonic acid	
<b>&lt; Properties &gt;</b>				
$\epsilon$ (*1)	@365 nm (i-line)	<b>400</b>	10000	500
	@405 nm (h-line)	0	<b>10000</b>	0
	@436 nm (g-line)	0	<b>400</b>	0
Solubility (wt%)	PGMEA	>20%	>20%	1%
	$\gamma$ -Butyrolacton	>20%	>20%	2%
Thermal decomposition temperature (*2)		>200°C		
<b>&lt; Function (Relative evaluation) &gt;</b>				
Photo decomposed ratio(*3)		<b>1.0</b>	<b>3.2</b>	1
Decomposed ratio in the presence of amine(*4)	Pyridine	< <b>0.01</b>	1.0	1
	Triethyl amine	< <b>0.01</b>	2.0	1

#### **< Evaluation methods >**

\*1 : 0.025 mM acetonitrile solution

\*2 : 5% weight loss temperature in TG-DTA analysis

\*3 : Calculated by HPLC, after the irradiation of High-pressure mercury lamp

\*4 : Calculated by NMR, PAG 1.5 parts and amine 1 parts, after storage for 24 hours

